

Supporting Information

Stabilization of organic field-effect transistors by *t*-butyl groups in dibenzotetrathiafulvalene derivatives

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1. XRD patterns

Figure S1 shows XRD patterns, where the *d* values are 12.5 Å for **1d**, 11.7 Å for **1e**, and 12.6 Å for **2**. The values for **1d** and **1e** are close to that for **1c**, indicating similar molecular packing, though the peak is unclear in **1e**. The *d* value for **2** does not simply correspond to the lattice constants of the single crystal (Table 2).

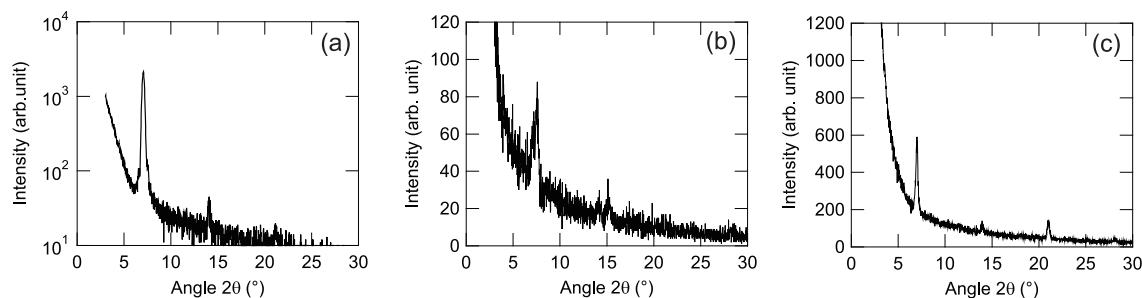


Figure S1. XRD patterns for the thin films of (a) **1d**, (b) **1e**, and (c) **2**, deposited on SiO₂.

2. AFM images

Figure S2 shows AFM images for **1d**, **1e**, and **2**. **1d** and **1e** consist of needle-like and block-like crystals, respectively. **2** consists of relatively fine crystals, and shows comparatively large spaces between the crystals.

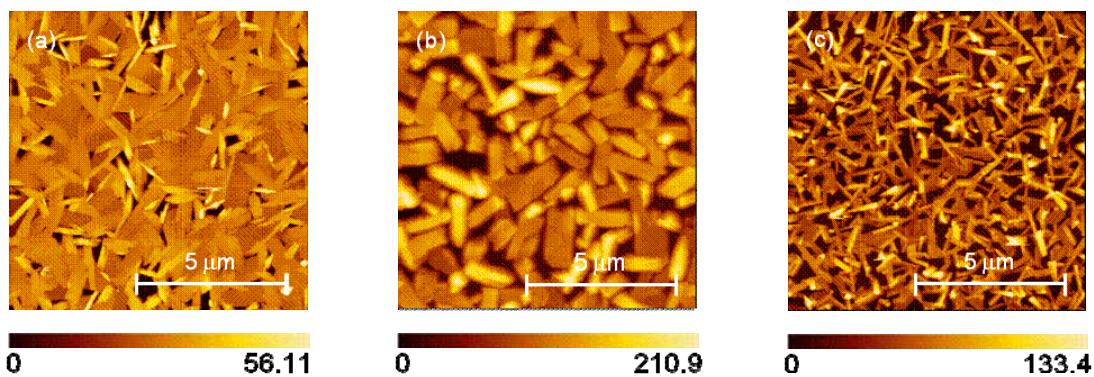


Figure S2. AFM images for the thin films (a) **1d**, (b) **1e**, and (c) **2**, deposited on SiO_2 deposited on SiO_2 .